

78. (New) An apparatus according to Claim 77, wherein said resonator comprises a pair of mirrors.

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79. (New) An apparatus according to Claim 78, wherein said pair of mirrors includes a total reflection mirror. --

REMARKS

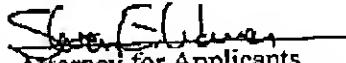
Applicants request favorable consideration and allowance of the subject application in view of the preceding amendments and the following remarks.

Claims 1, 2, 4-8, 10-15, 17-20, and 30-79 are presented for consideration. Claims 1, 13, 20, 30, 46, 55, 56, 58-60, 62, 64-66 and 73 are independent. (Claims 56-59 were added in a Supplemental Preliminary Amendment filed on December 4, 2001.) Claims 60-79 have been added herein to recite additional features of the subject invention. Support for these claims can be found in the original application as filed. Therefore, no new matter has been added.

Claims 1, 2, 4-8, 10-15 and 17-55, and presumably claims 56-59, were previously allowed in this application. In addition to these claims being allowable, Applicant submits that claims 60-79 patentably define features of the exposure apparatus, the gas laser device, and the semiconductor device manufacturing method of the present invention. Therefore, Applicants submit that the instant application is in condition for allowance. Favorable consideration and an early Notice of Allowance are requested.

Applicants' undersigned attorney may be reached in our Washington, D.C. office by telephone at (202) 530-1010. All correspondence should be directed to our address listed below.

Respectfully submitted,



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